

YES Vapor Prime Oven SOP

1. Scope

1.1 This document provides the procedure for operating the Yield LP III HMDS Vapor Prime Oven.

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3. Reference Documents

3.1 Referenced within this Document

3.1.1 None

3.2 External Documents

3.2.1 None

4. Equipment and/or Materials

4.1 YES Vapor Prime Oven

4.2 Wafer/Sample

4.3 HMDS

5. Safety

5.1 Follow all Nanofab safety procedures.

6. Setup Procedures

6.1 Check the status of the system: See *Figure 2, Control Panel*.

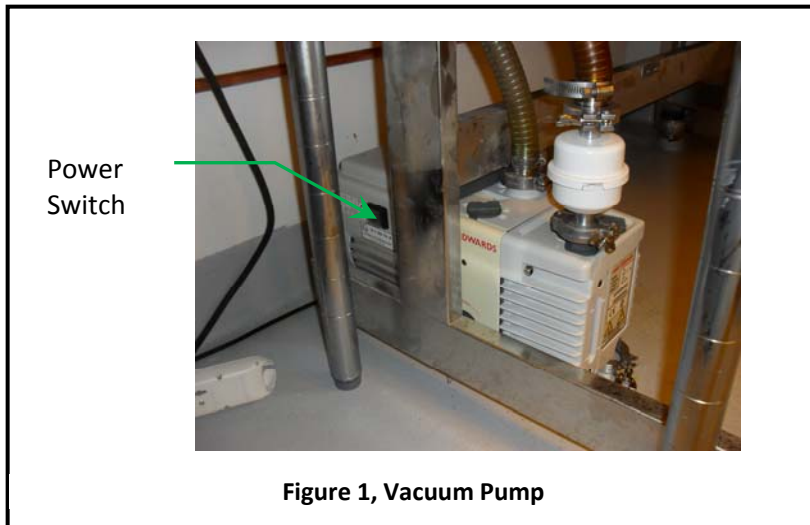
6.1.1.1 Vacuum Gauge: <100 Torr

6.1.1.2 Temp. ~150 C

6.1.1.3 HMDS in flask

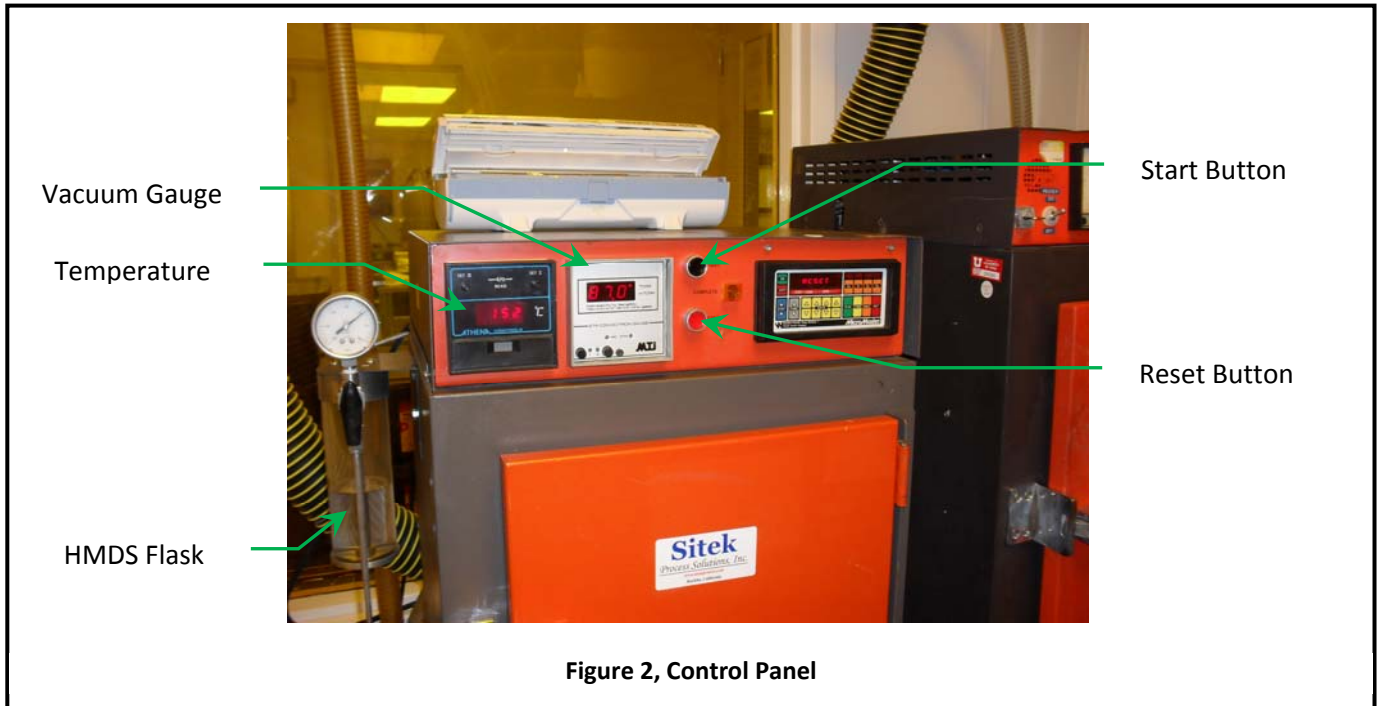
6.1.1.4 Vacuum pump off

- 6.2 Turn on vacuum pump. See *Figure 1, Vacuum Pump*.
- 6.3 Press the black START button. This will vent the system for 5 minutes. See *Figure 2, Control Panel*.



7. Film Deposition Procedures

- 7.1 Pull the door open and insert wafers.
- 7.2 Close the door. This may require a bit of force.
- 7.3 Press the black START button again.
NOTE: This will start pump down and deposition process. The total time is ~30 minutes.
- 7.4 An alarm will sound when the run is finished.
- 7.5 Press the black START button again to vent the system.
- 7.6 Pull the door open and remove samples.
- 7.7 Close the door and press the black START button.
- 7.8 Once the vacuum gauge reads lower than 100 Torr, press the red RESET button. See *Figure 2*.
NOTE: This will stop the system. Make sure this is done before the next step or it will begin a nitrogen backfill.
- 7.9 Turn off the vacuum pump.



8. Revision History

Rev	Date	Originator	Description of Changes
1	14 Jan 2010	Sam Bell	